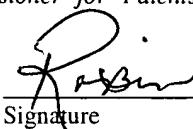




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Signature

Appl No.	: 10/625,316	Confirmation No. 7750
Applicant	: Sriram Venkatasanthanam, et al.	
Filed	: July 23, 2003	
Title	: METHOD FOR FORMING INHERENTLY INK-RECEPTIVE FILM SUBSTRATES	
TC/A.U.	: 1732	
Examiner	: Mark Eashoo	
Docket No.	: 50770/A23	
Customer No.	: 23363	

RESPONSE

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Post Office Box 7068
Pasadena, CA 91109-7068
November 10, 2006

Commissioner:

This is in response to the Office action dated July 10, 2006. Claims 1-5 are pending in the application. Claims 1-4 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Freedman (US 4,713,273) in view of Yamamoto et al. (US 3,551,538). It appears that claim 5 is also rejected based on the same combination. For the reasons that follow, Applicants respectfully traverse the rejection and request reconsideration.

The Examiner states that "Freedman teaches the basic claimed process of forming an ink receptive substrate comprising: forming a melt processable base layer from a water insoluble thermoplastic polymer (9:65-10:45) and Fig. 6); and coextruding a bas[e] layer and skin or ink receptive layer (9:20-11:10)." The Examiner acknowledges that Freedman does not teach an ink receptive layer formed from a polyolefin and polyethylene oxide.